



US00D424583S

United States Patent [19]

[11] **Patent Number: Des. 424,583**

Mizukami

[45] **Date of Patent: ** May 9, 2000**

[54] **HINGE UNIT FOR VACUUM-PROCESSING A SEMICONDUCTOR WAFER**

| | | | | |
|-----------|---------|---------------|-------|-----------|
| 1,120,163 | 12/1914 | Sanders | | 16/354 |
| 4,011,628 | 3/1977 | Bengtsson | | 16/354 X |
| 4,923,054 | 5/1990 | Ohtani et al. | | 414/937 X |
| 5,195,210 | 3/1993 | Lee | | 16/354 X |

[75] Inventor: **Masami Mizukami**, Kofu, Japan

[73] Assignee: **Tokyo Electron Limited**, Tokyo, Japan

Primary Examiner—Alan P. Douglas
Assistant Examiner—Lavone D. Tabor
Attorney, Agent, or Firm—Oblon, Spivak, McClelland, Maier & Neustadt, P.C.

[**] Term: **14 Years**

[21] Appl. No.: **29/086,850**

[22] Filed: **Apr. 21, 1998**

[57] CLAIM

[30] Foreign Application Priority Data

Oct. 21, 1997 [JP] Japan 9-72009

The ornamental design for a hinge unit for vacuum-processing a semiconductor wafer, as shown.

[51] **LOC (7) Cl.** **15-09**

DESCRIPTION

[52] **U.S. Cl.** **D15/122; D8/323; D15/138; D15/141**

FIG. 1 is a front elevational view of hinge unit for vacuum-processing a semiconductor wafer, showing my new design;

[58] **Field of Search** D13/182; 414/217, 414/935, 937; 16/221, 244, 354; 49/149, 152, 153, 246, 247, 254; D15/122, 138, 141; D8/323

FIG. 2 is a top plan view thereof;
FIG. 3 is a bottom plan view thereof;
FIG. 4 is a right side elevational view thereof;
FIG. 5 is a rear elevational view thereof; and,
FIG. 6 is a left side elevational view thereof.

[56] References Cited

U.S. PATENT DOCUMENTS

D. 139,795 12/1944 Terry D15/138

1 Claim, 2 Drawing Sheets

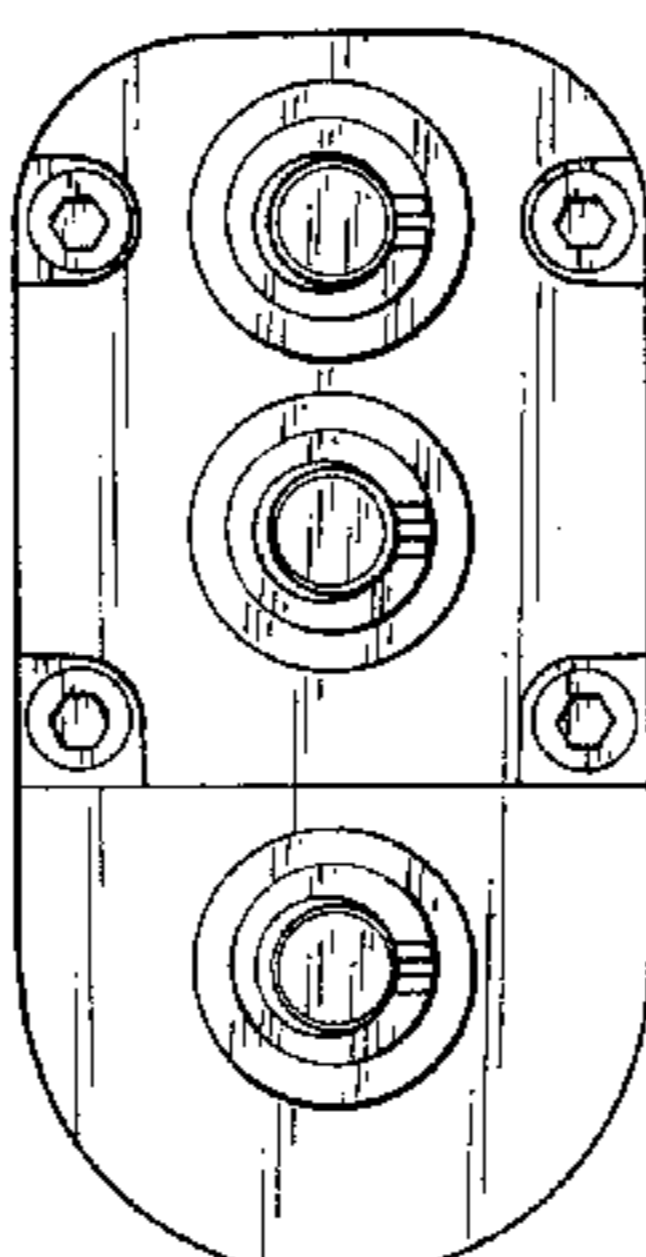
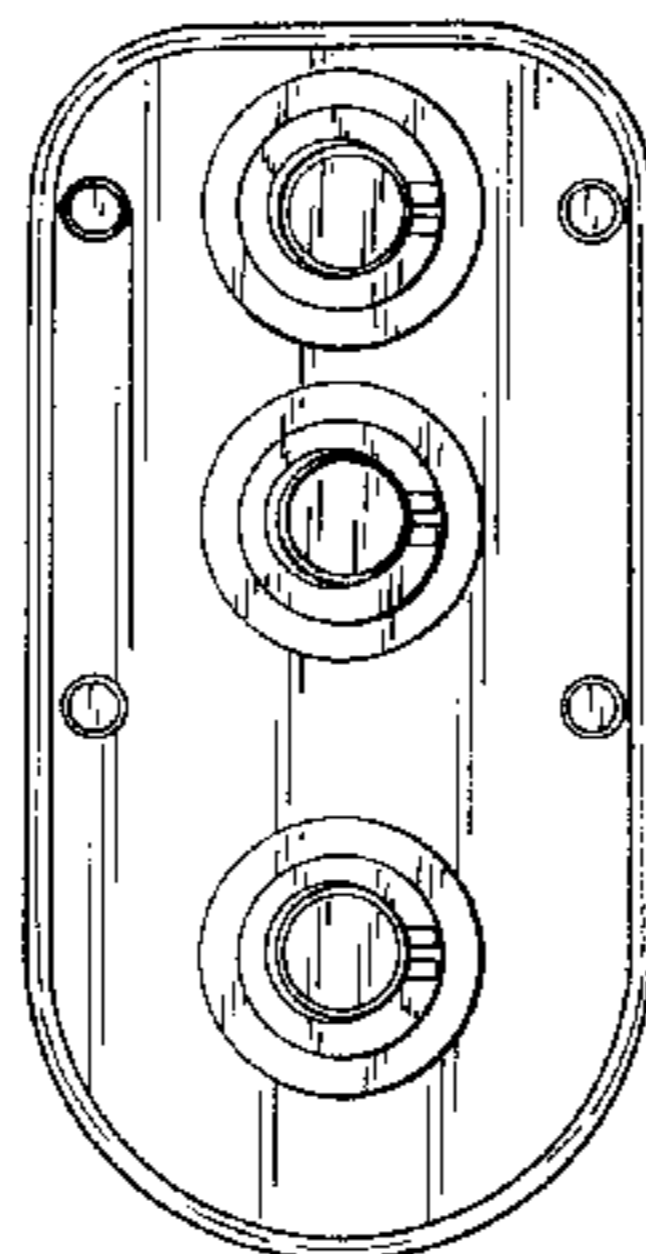
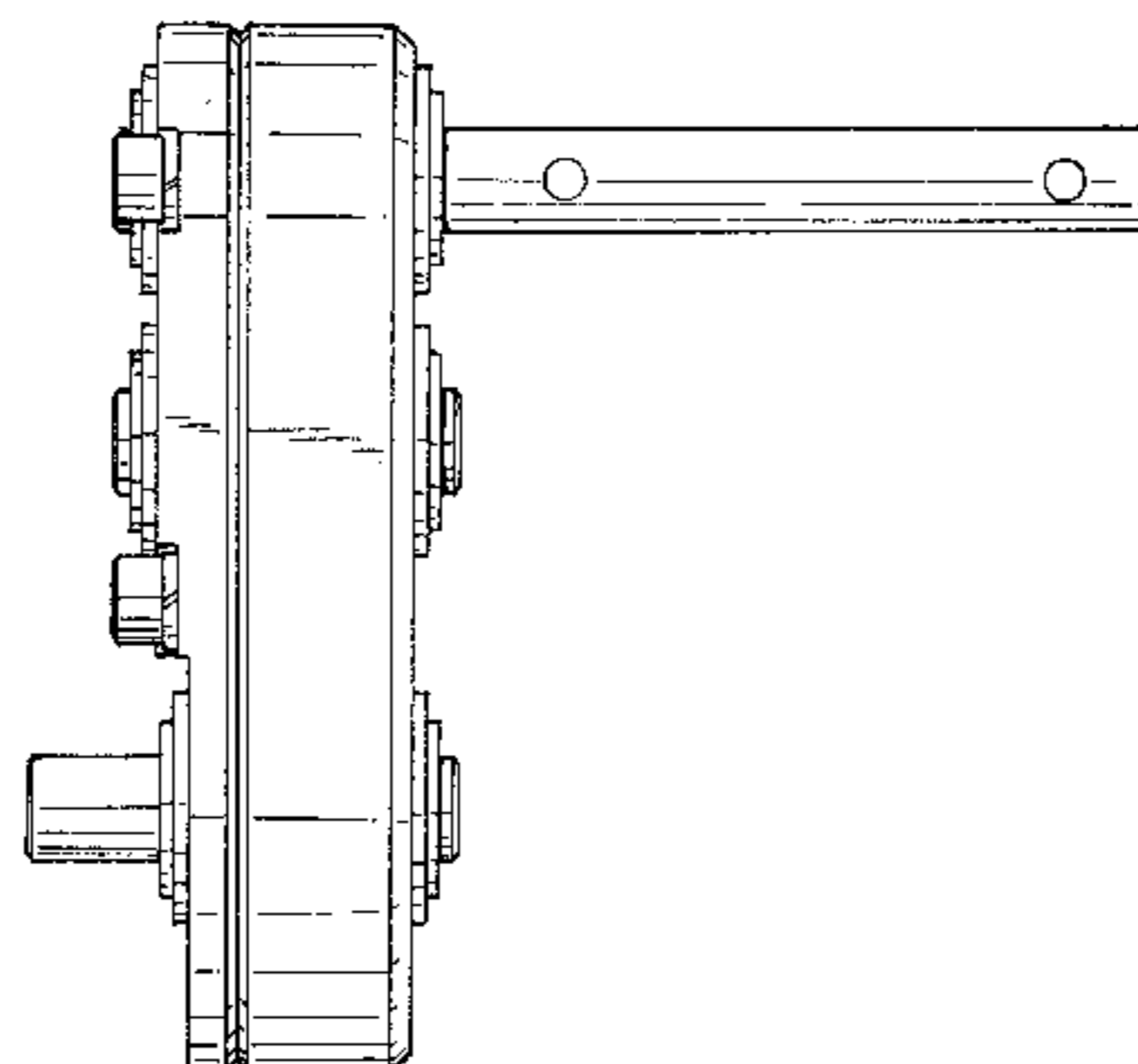


FIG. 2

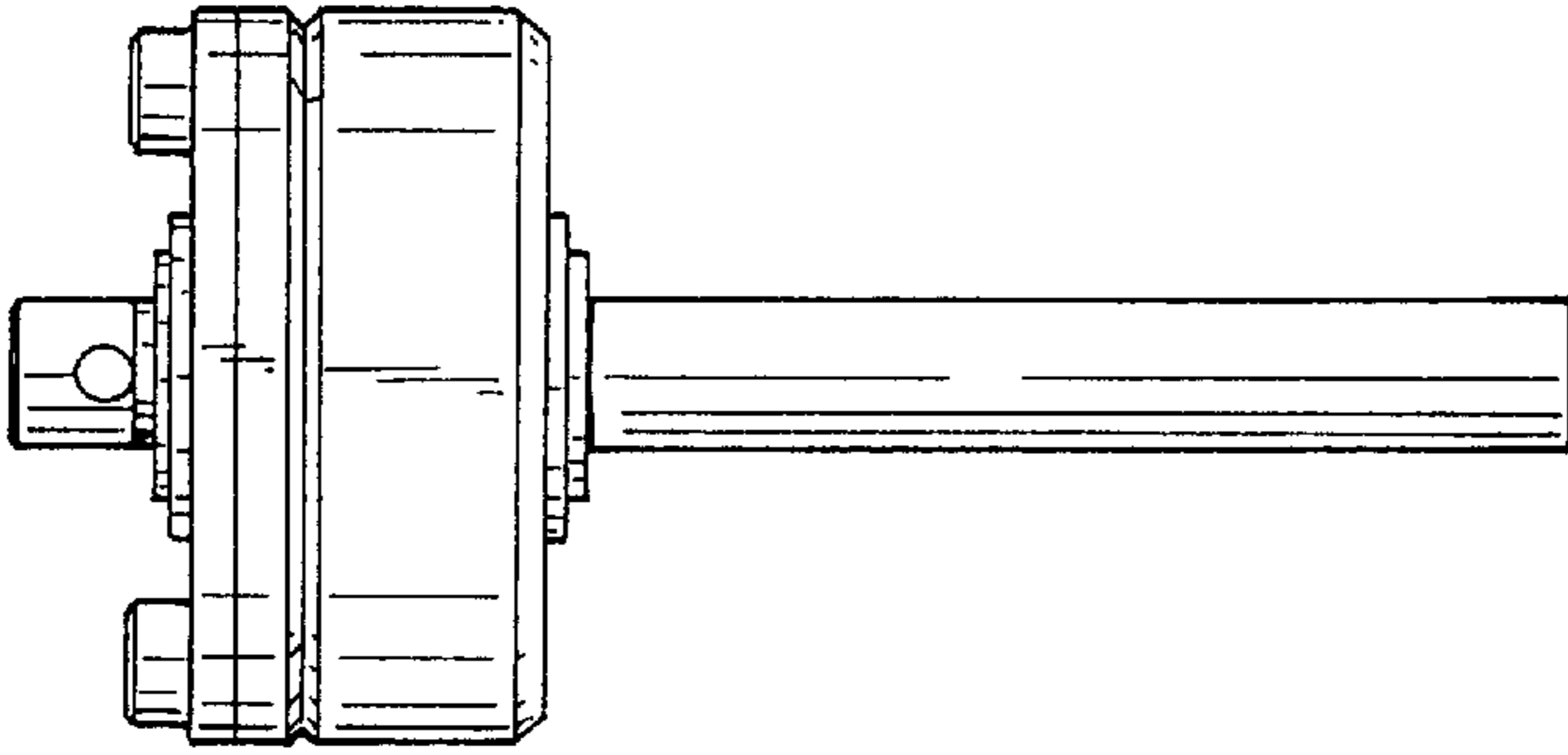


FIG. 1

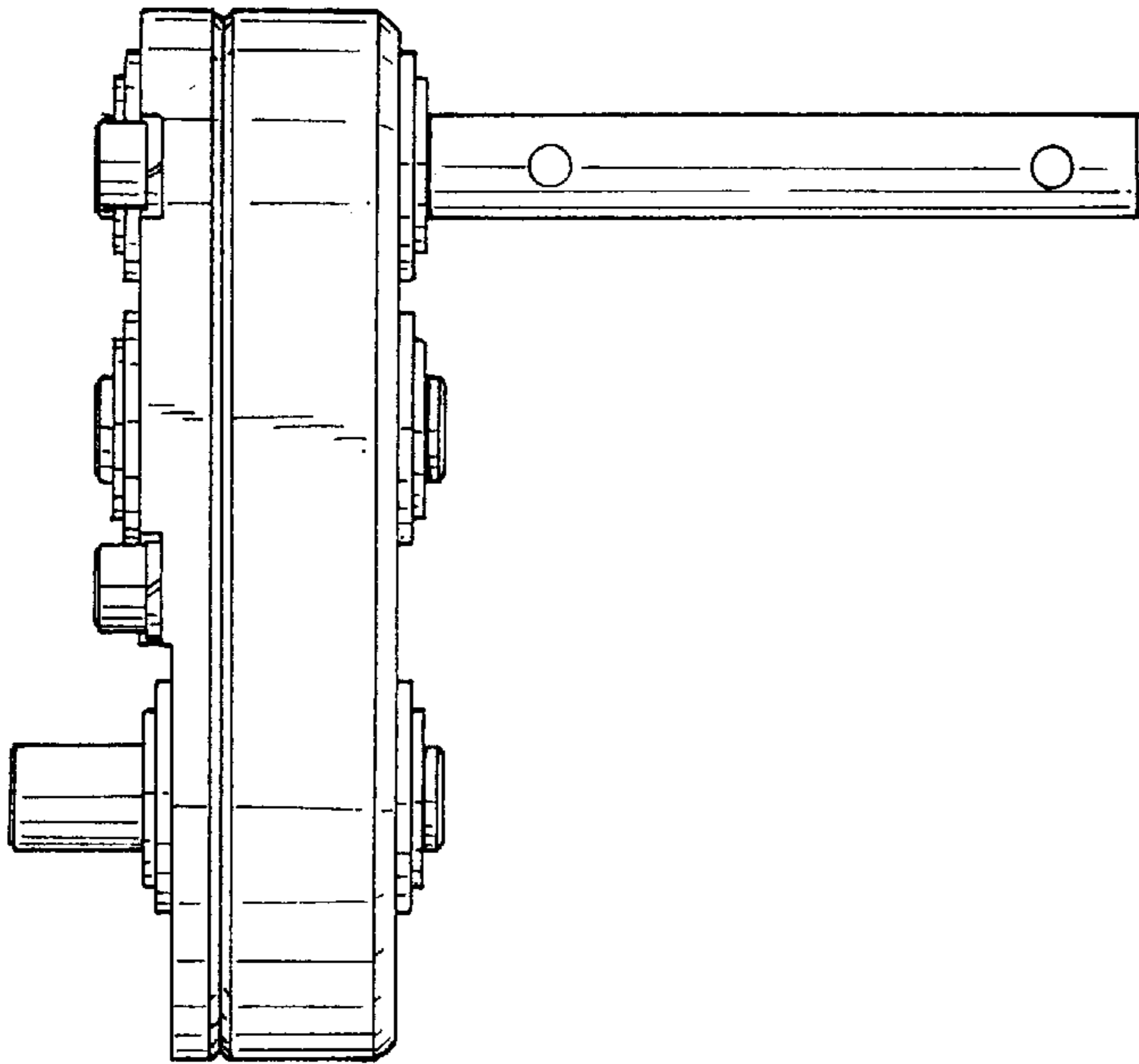


FIG. 4

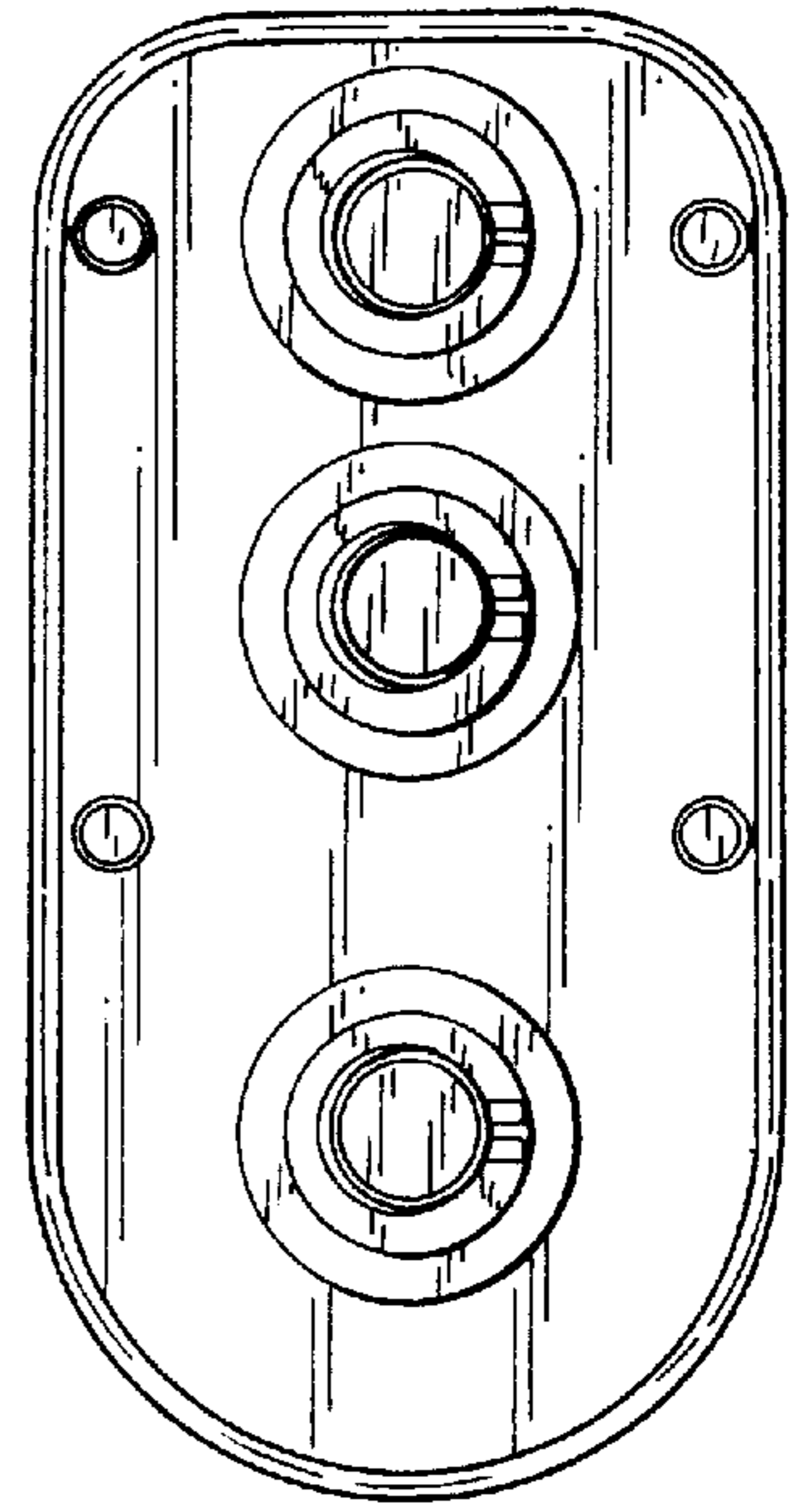


FIG. 3

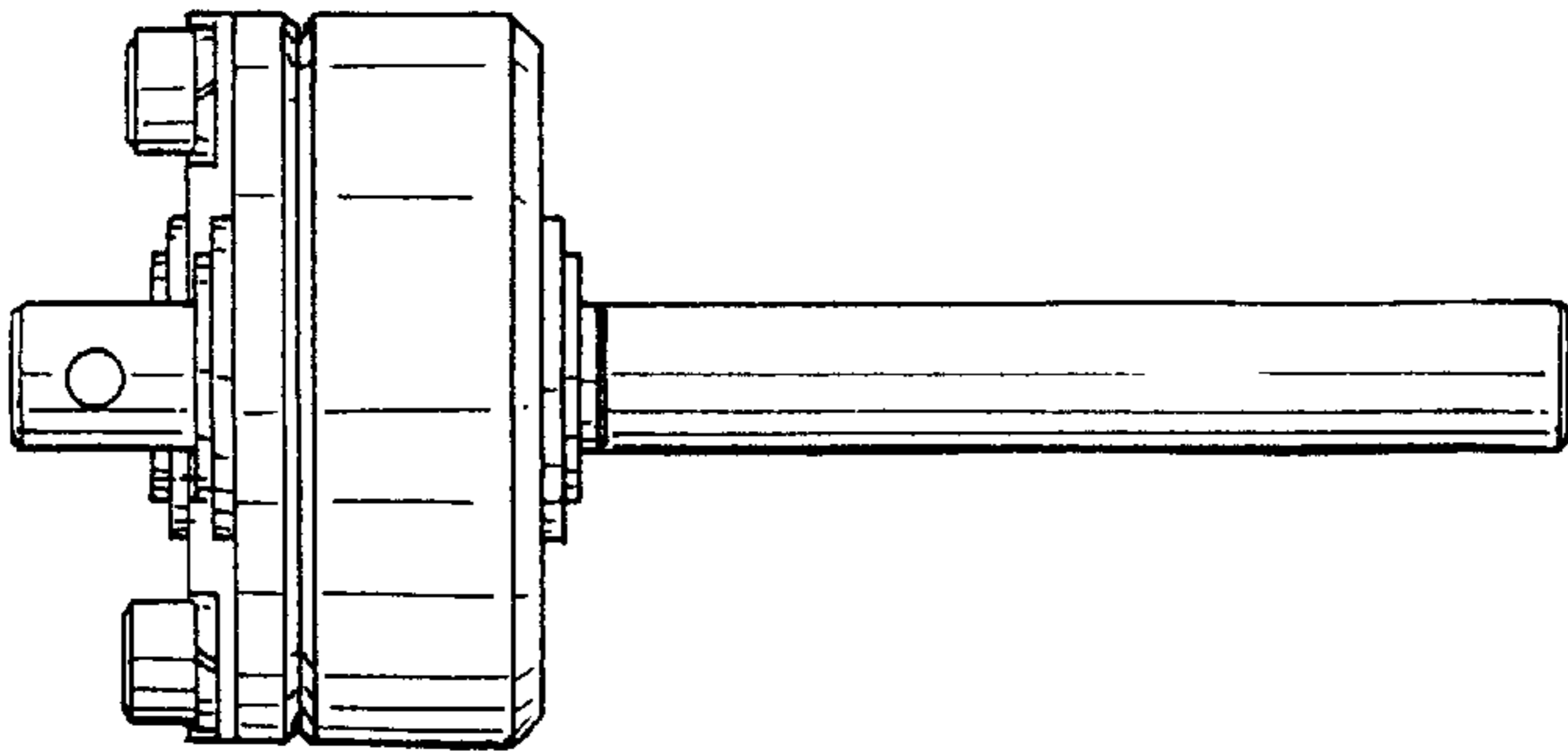


FIG. 5

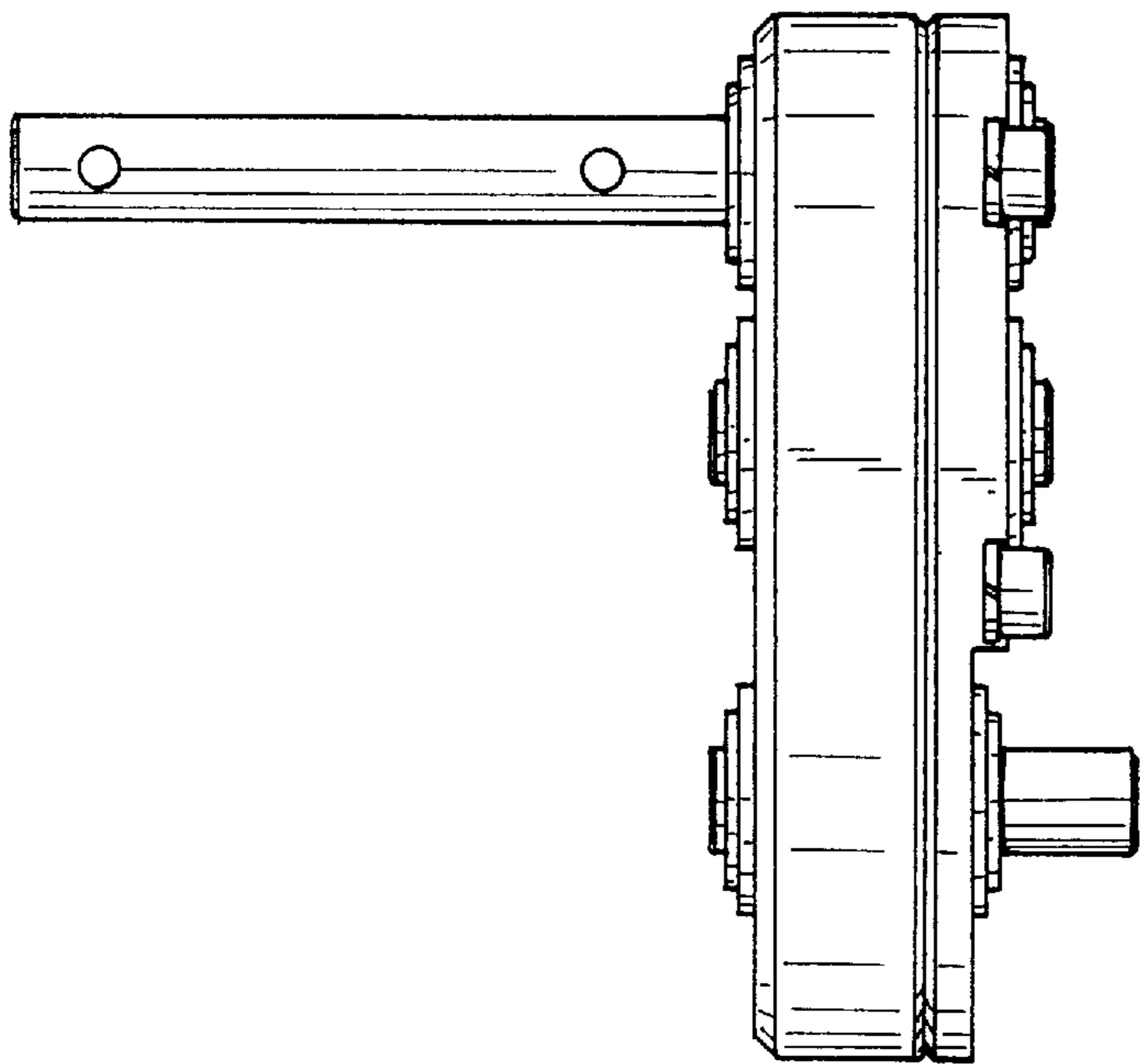


FIG. 6

